

IN THE CLAIMS

Per the revised amendment practice, a complete listing of all claims in the application follows.

Claims 1-36 (Canceled).

37. (original) An atmosphere for a chemical vapor deposition process, comprising:
a deposition gas having a pressure contribution and a chemical reactability; and
a chemically inert gas mixed with said deposition gas, limiting said pressure
contribution of said deposition gas, and increasing said chemical reactability of
said deposition gas.

38. (original) The atmosphere of claim 37 wherein said deposition gas is a film precursor
deposition gas.

39. (original) The atmosphere of claim 37 wherein said deposition gas is a metal film precursor
deposition gas.

Claims 40-66 (cancelled).